

Tin Whiskers: Attributes and Mitigation





CARTS Europe

October 2002 Nice, France

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Outline

- Why ANOTHER Paper on Tin Whiskers?
- What are Tin Whiskers?
 - Attributes
 - Examples
 - Failure Modes
- Experience History
- Tin Whiskers on Ceramic Capacitors (MLCCs)
- Whisker Mitigation Strategies
- Conclusions & Recommendations





Why **ANOTHER** Paper on Tin Whiskers?

- The PAST:
 - Tin Whiskers Known for ~60 Years
 - HUNDREDS of Independent Studies
 - Numerous Disparities Exist in Published Literature
- The PRESENT: Combination of CONCERNING Factors

Electronics Industry Conversion to Pure Tin Finishes Due to Pending Pb-Free Legislation

Lower Application Voltages

SMALLER Circuit Geometries

No Consensus Understanding of Whisker Growth Mechanism(s)

No "Accepted"
Accelerated Whisker Tests

"New" Discoveries of Whisker-Prone Items



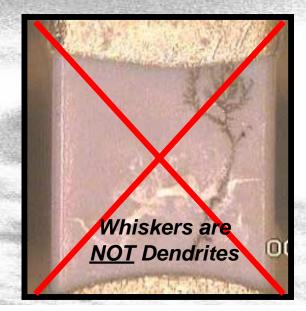




What are Tin Whiskers?

- "Hair-Like" Single Crystal
 Structures that May Grow from
 Tin Finished Surfaces
- LENGTH: Up to 10 mm (Typically < 1mm)
- DIAMETER: from 0.006 to 10 μm (Typical ~ 1 μm)
- Grow from the Base Not the Tip
- <u>Mechanical Stress Relief</u> and Diffusion Processes in Tin Finish Drive Whisker "Extrusion"

Fundamental Research is INCOMPLETE









Factors that Influence Whisker Growth

Plating Chemistry

Pure Sn Most Prone Some Alloys (Sn-Cu, Sn-Bi, rarely Sn-Pb)

Use of "Brighteners"
Incorporated Hydrogen
Codeposited Carbon

Plating Process

High Current Density Bath Temperature Bath Agitation

Deposit Characteristics

Grain Size/Shape
Crystal Orientation
Deposit Thickness
Sn Oxide Formation

Substrate

Material (Brass, Cu, Alloy 42, Steel, etc.)
Substrate Stress (Stamped, Etched, Annealed)
Intermetallic Compound Formation
Substrate Element Diffusivity into Sn

In General,
Factors that
Increase STRESS
In Tin Deposit

GREATER WHISKER PROPENSITY

Environment

Temperature
Temperature Cycling (CTE Mismatch)
Humidity (Oxidation, Corrosion)
Applied External Stress
(Fasteners, bending, scratches)

HOWEVER....

Many Experiments Show Contradictory Results For These Factors







Sneaky Tin Whiskers!!!

Incubation Period (DORMANCY)

Initiation of growths may occur...

- As Short as a Few Days after Plating, or
- AS LONG AS MANY YEARS!!!



Growth Rate

- Up to 9 mm/yr
- Typically Substantially SLOWER!!!

These Attributes are UNPREDICTABLE thus Presenting a MAJOR Challenge

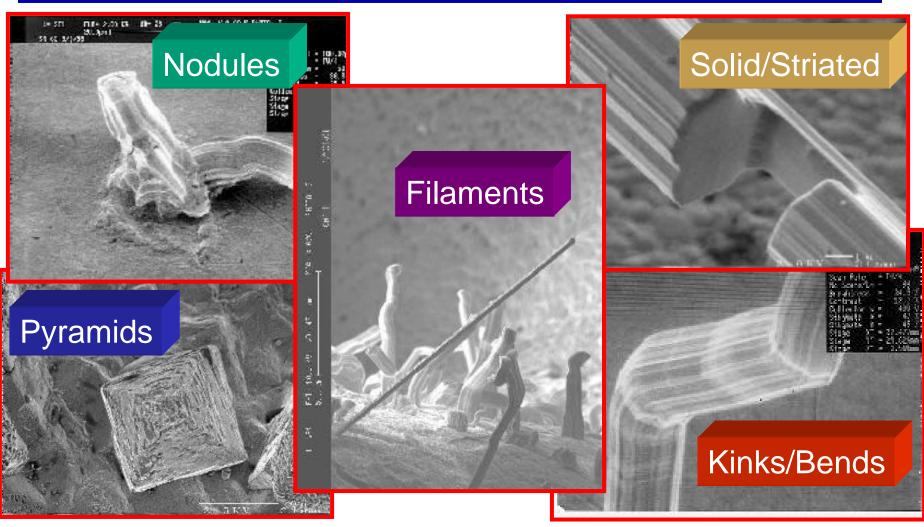






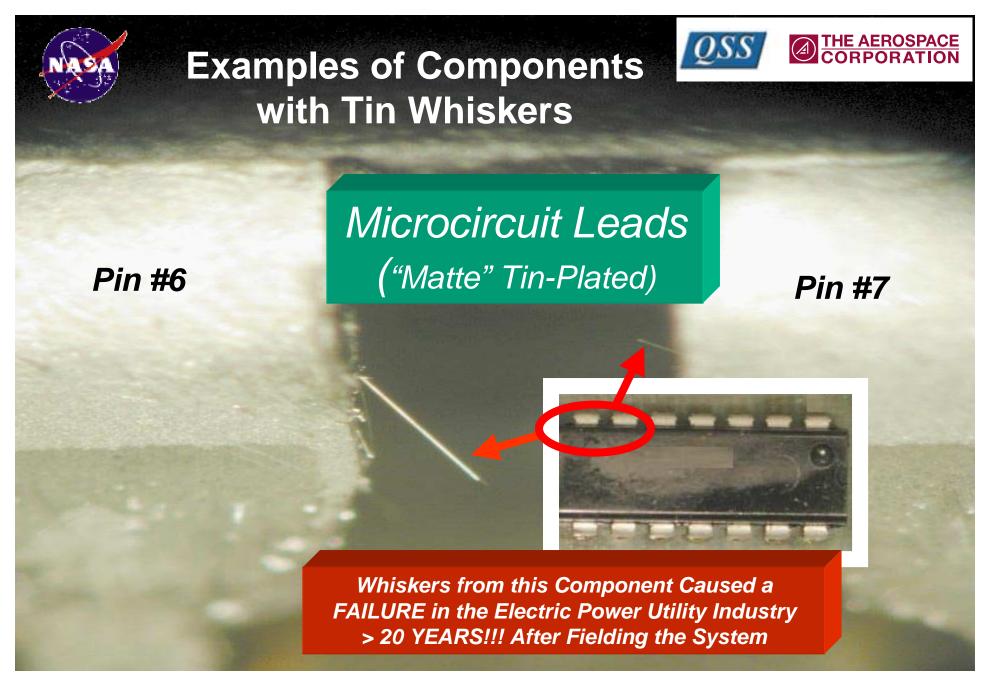


Whisker Shapes & Features

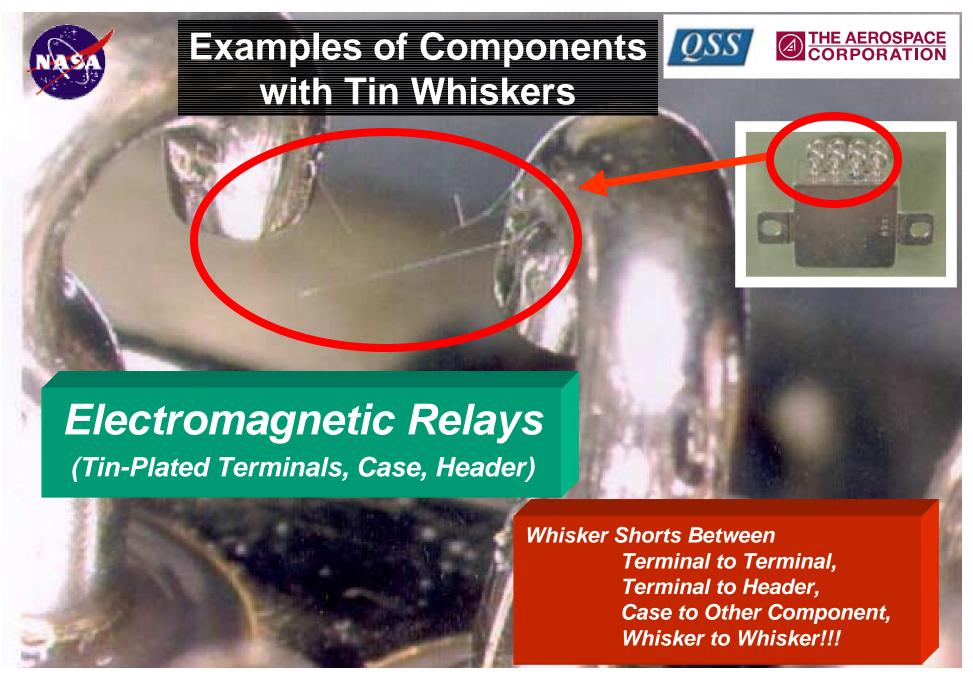


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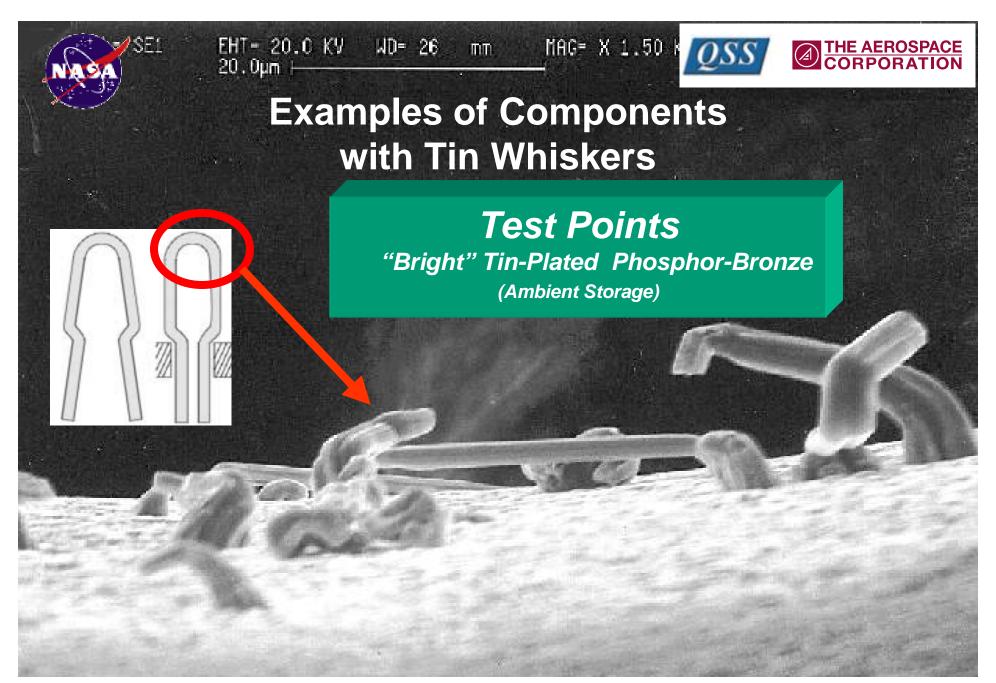
Tin Whiskers: Attributes and Mitigation

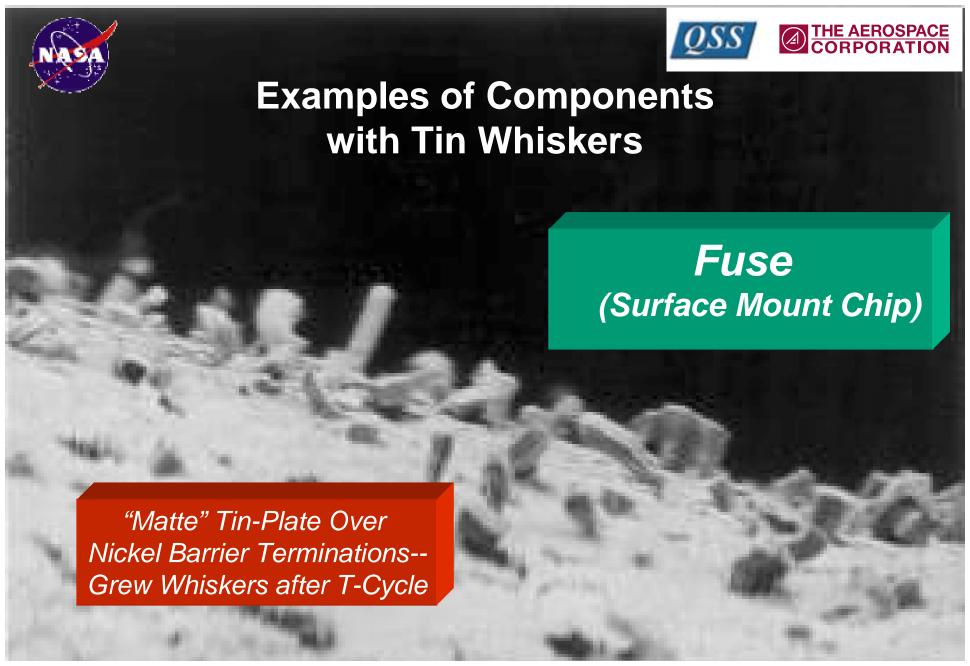


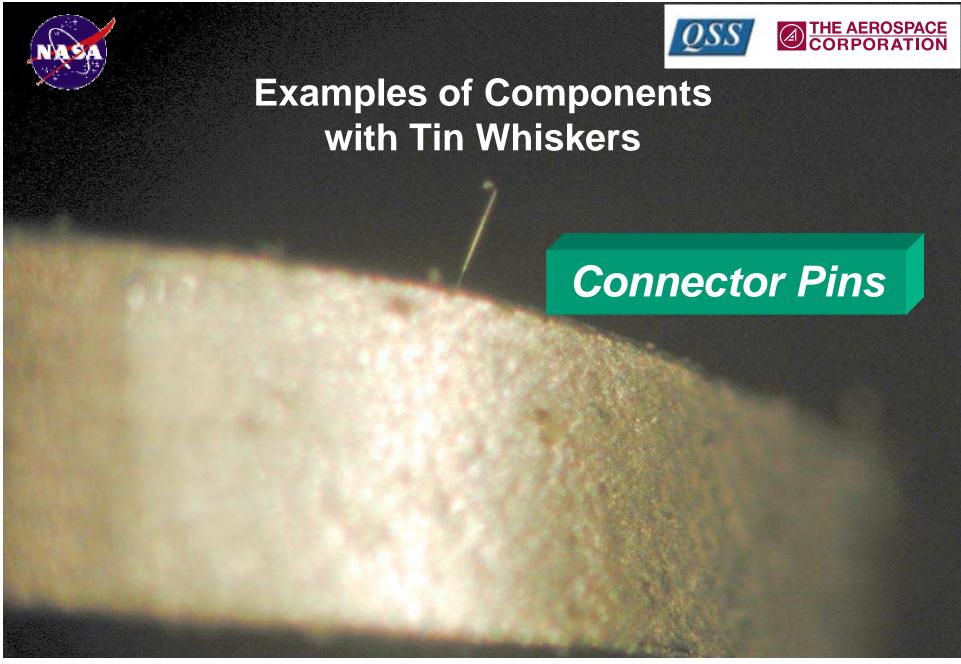














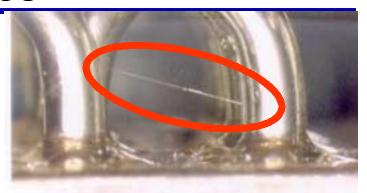
Tin Whisker Failure Modes





Electrical Short Circuits

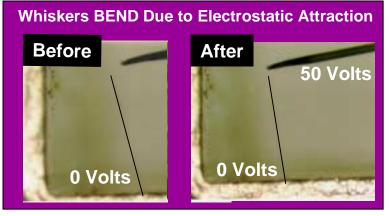
- Permanent (current < 10's of mA)
- Intermittent (current > 10's of mA) Whisker Melts



Debris/Contamination

- Interfere with Sensitive Optics or MEMS
- Shorts in Areas Remote From Whisker Origins

METAL VAPOR ARC in VACUUM



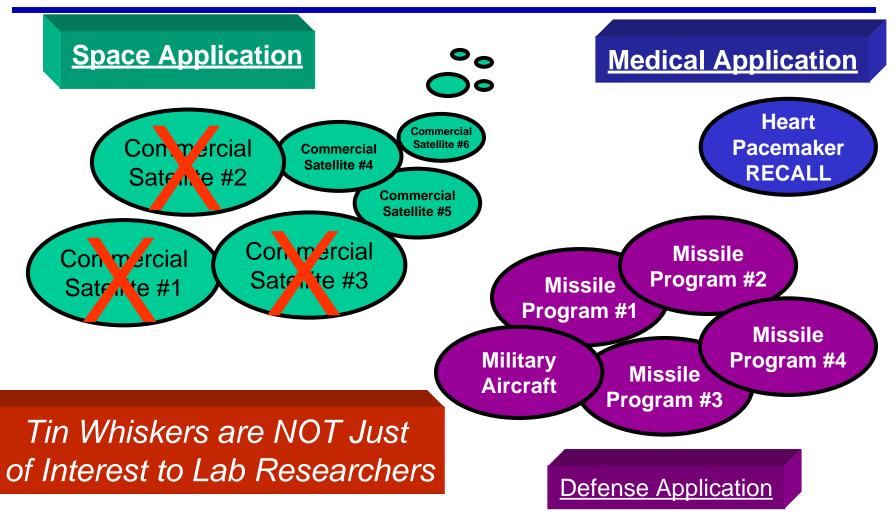
- Atmospheric Pressure < ~150 torr, Whisker Short can Vaporize into Highly Conductive PLASMA of Tin Ions if V > ~18 V and I > 10's of Amps
- Plasma can Form Arc Capable of Carrying <u>HUNDREDS OF AMPERES</u>
- Arc Can Be Sustained by Tin Evaporated from Surrounding Areas







"Reported" Tin Whisker-Induced Field Problems









Tin Whiskers and Multilayer Ceramic Capacitors (MLCCs)

Past Research

 Two Previous Papers by MLCC Manufacturers (1990 & 1997) Assert MLCCs Have Following Attributes that make them Highly Resistant to Whisker



"Large" Tin Grain, Well-Polygonized >5 μm



Ni-Underplate (> 2 μm)

Reduces Diffusion that Causes Internal Stress



"Thick" Matte Tin Plating
5 - 10 μm

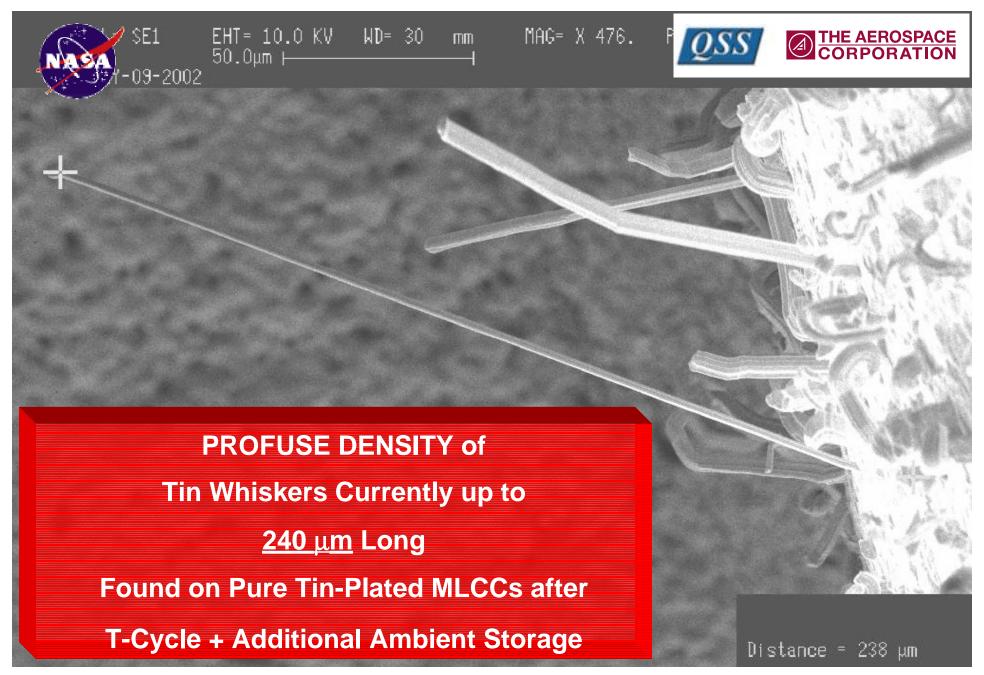


Post-Plating Annealing

Promotes Grain Growth & Reduces Residual Stress

ONE MLCC Mfr Experiment showed <u>18 Years WHISKER-FREE</u>
 Observations for MLCCs Stored Continuously at 50°C

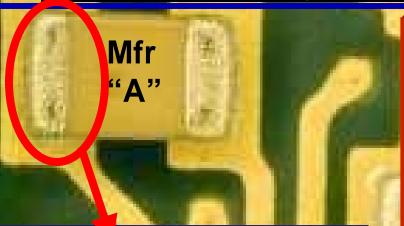
HOWEVER ...





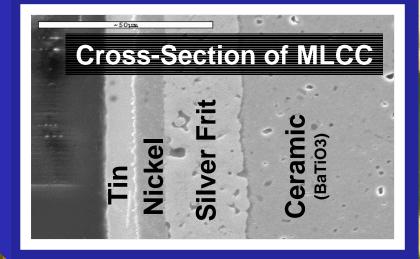


Example #1: Tin Whiskers and MLCCs MLCCs Inside Hybrid Microcircuit After T-Cycle



User Application:

- Hybrid Microcircuit (Herm-Sealed)
 - Gold Plated Substrate Pads
 - Substrate Line Spacing 125 μm (min.)
- ORDERED Pd-Ag Terminated MLCC, but Supplier Shipped <u>PURE TIN</u>
- Silver Epoxy Mounting Method



MLCC Construction (0805 size):

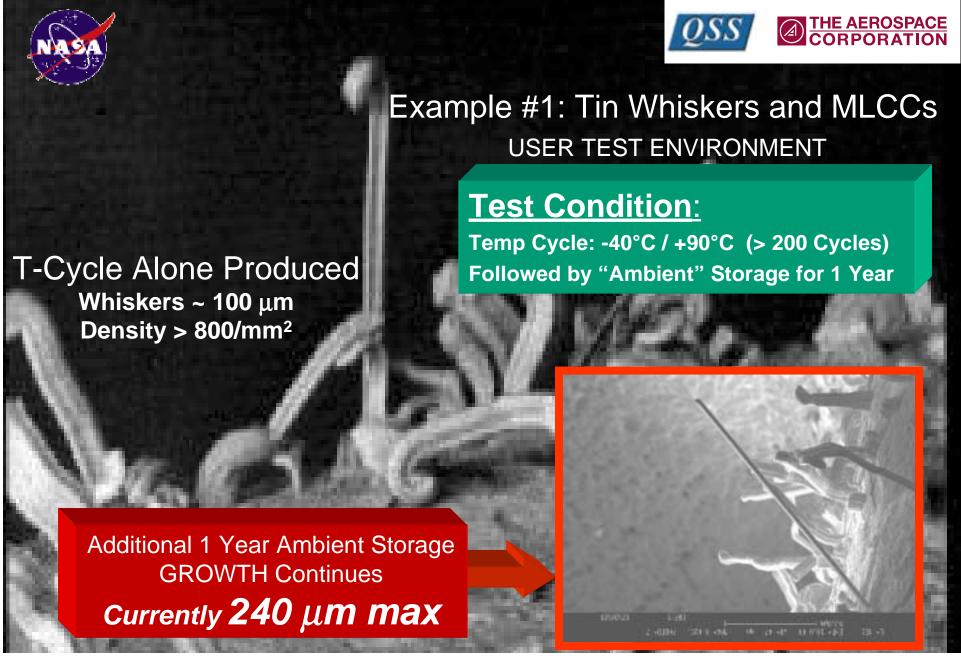
Barium Titanate Ceramic Body

Silver Frit Base Termination17 μm

🖊 *Nickel Barrier Layer* 6.5 μm

Matte Tin-Plated Final Finish 6.5 μm

Average Grain Size > 5 μm



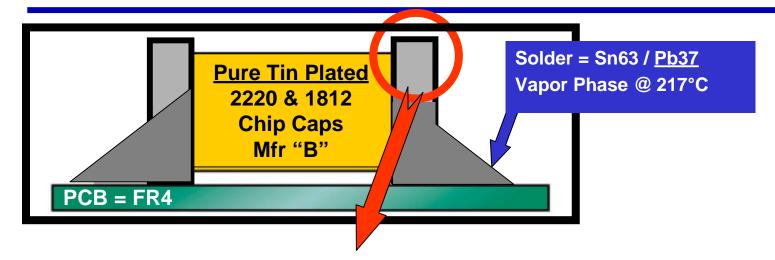






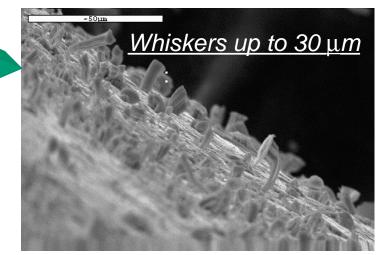
Example #2: Tin Whiskers and MLCCs

Whiskers AFTER Vapor Phase Installation and T-Cycle



<u>Test Condition</u>: Temp Cycle/Shock -55°C / +100°C (50 - 400 Cycles)

Soldering Operations DO NOT
Always Reflow ALL Tin Surfaces
Nor Mix them with the Mounting Solder



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Tin Whiskers: Attributes and Mitigation







User Whisker Mitigation

Research on User-Mitigation Strategies is Limited

- Most Approaches Come with Benefits & <u>Limitations</u>
- Long-Term Effectiveness NOT Quantified

Strategies to Consider (Complete Immunity NOT Guaranteed)

- REDUCE STRESS in the Tin Plating
 - Hot Oil Reflow / Hot Solder Dip (Preferably with Sn/Pb Solder)
 - High Temp Anneal Substrate and Tin Finish
 - Underplate with Diffusion Resistant Barrier May Delay Onset
- USE PHYSICAL BARRIERS to Insulate Against Potential Shorts
 - Conformal Coat or other Insulating Barriers
 - Increase Spacing of Surfaces of Opposite Polarity to > 0.5 inches
- MINIMIZE REINTRODUCING STRESS thru Handling, Assembly & Application

Combine MULTIPLE Mitigation Strategies to Increase Effectiveness

AVOID PURE TIN, if Possible



Whisker Mitigation Conformal Coat (Polyurethane)





NASA Goddard Experiments
(>3 Years Observation at 50°C & Room Ambient)

- NO Whiskers THRU 50 μm Thick Uralane 5750
- Conformal Coat REDUCES (but does NOT Eliminate)
 Rate of Whisker Growth Compared to Uncoated Specimen
- Whiskers Have Grown thru ~2 to 6 μm THIN Uralane 5750
 After 2.5 Years of Ambient Storage

Whisker Nodule BENEATH
50 µm thick Conformal Coat









Conclusions

Failures Due to Tin Whiskers are <u>STILL</u> a Significant Problem

PROBLEMS WILL INCREASE with Increased Use of Pure Tin Coatings Until
Significant Discoveries are Made Regarding Effective Mitigation Practices

Factors Affecting Tin Whisker Formation are NOT Completely Understood

Risk Assessment Based on <u>SUBSET</u> of Published Literature Can Be <u>DANGEROUS</u>

Tin-Plated Ceramic Chip Capacitors <u>ARE</u> Susceptible to Whisker Formation

<u>CONTRARY</u> to Previously Published Claims

Even when PROHIBITED by Design and Procurement Practices, Pure Tin Finishes Continue to Appear in Electronic Equipment

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Recommendations

Develop CONSENSUS Model(s) of Whisker Growth Mechanism(s)

- MORE than One Mechanism is Likely
- Model Needed to have Confidence in Any Proposed Accelerated Test

Develop PROVEN "Whisker Propensity" Test(s)

- Environmental Testing vs. Finish Characterization??
- Acceleration Factors MUST be Determined
- Tailorable to Assess Varied Constructions, Materials AND Applications

Share Whisker Experiences and Knowledge More OPENLY

- Education vs. MIS-Information
- Collaboration

Develop Whisker Risk Assessment & Mitigation Strategies

- Plating Chemistry/Process Suppliers Electronic System Mfrs

Component Mfrs

End Users







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NASA Goddard Tin (and Other Metal) Whisker WWW Site

http://nepp.nasa.gov/whisker





GROWTH RINGS

Tin Whiskers Grown on Ceramic Chip Capacitor Via Temp Cycling (-40°C to +90°C)

During a reliability study at NASA's Jet Propulsion Laboratory,uniform whisker growth steps were observed and correlated with thermal cycles. This work is on-going and results will be published in the near future. The investigation was performed by Wayne Bosze and Saverio D'Agostino of the Electronic Parts Engineering Section.

Photo Courtesy of NASA Goddard Space Flight Center

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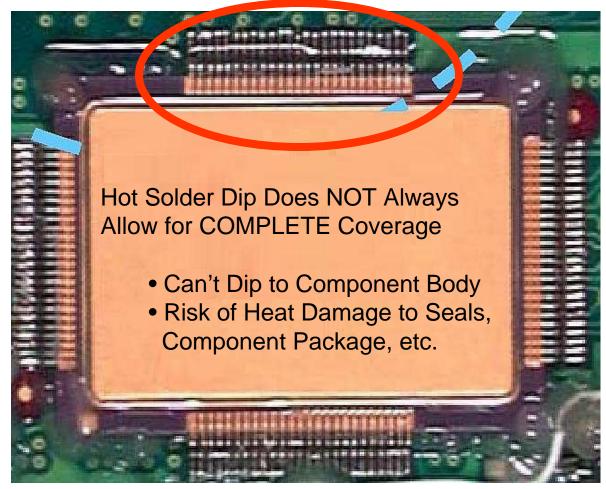


BACKUP MATERIAL





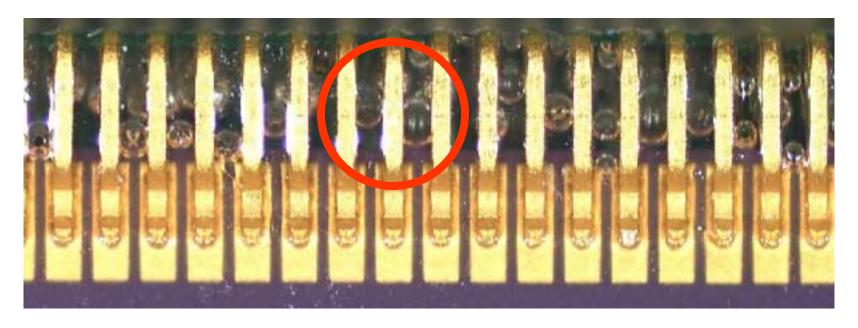
Some LIMITATIONS of Mitigation Strategies--Hot Solder Dip







Some LIMITATIONS of Mitigation Strategies--Conformal Coat



Conformal Coat

- Air Bubbles Enable Path For Whisker Shorts??
- Can You Cover Underside of Flush Mount Devices??
- Can You Control Uniformity of Coverage/Thickness??

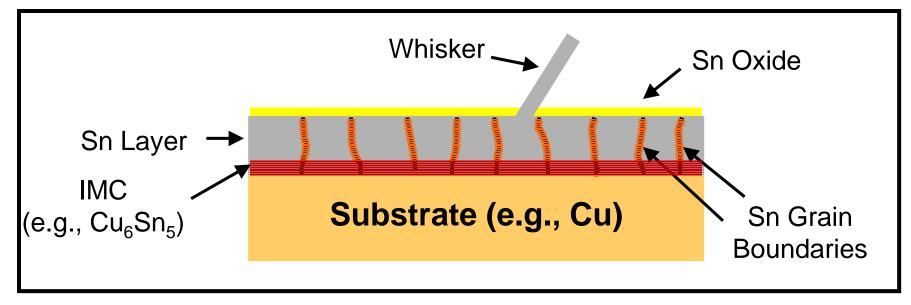






One Model for Whisker Growth Mechanism

- 1. Substrate Elements (Cu, Zn, etc.) Diffuse into Sn Along Grain Boundaries.
- 2. Intermetallic Compound (IMC) may form preferentially in Grain Boundaries
- 3. As a Result, Stress Builds in Sn Layer
- 4.To Relieve Stress, Whiskers EXTRUDE thru Ruptures in Sn Oxide



NASA Goddard Space Flight Center Tin Whisker Test Coupon

December 1998



Underplate: some specimens with copper strike and copper plate to 0.0001" min

some specimens with NO copper underplate (i.e., tin direct on brass)

Finish: "Bright" Pure Tin Electroplate (200 ± 50 microinches)

Post-Plating Handling: "Intentional" Scratches (circle and perpendicular lines)

